

AMENDMENTS TO THE CLAIMS

1. (Withdrawn)

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20. (Amended) A process for coating of substrates comprising:

inserting a substrate into a process chamber;

supplying a first chemical to a heated vaporization chamber;

vaporizing said first chemical; and

supplying the vapor of said first chemical to a process chamber, thereby coating said substrate
with said first chemical.

21. (Original) The process of claim 20 further wherein said supplying a first chemical comprises
withdrawing said first chemical from a first chemical reservoir.

22. (Original) The process of claim 21 wherein said withdrawing said first chemical comprises
withdrawing a specific volume of said first chemical from said first chemical reservoir.

23. (Original) The process of claim 21, wherein said first chemical reservoir is a chemical
manufacturer's source bottle.

24. (Original) The process of claim 20 further comprising dehydrating a substrate.
25. (Original) The process of claim 24, wherein said dehydrating a substrate comprises:
- inserting said substrate into said process chamber;
 - evacuating said chamber to a first pressure;
 - inputting a first gas into said process chamber.
26. (Original) The process of claim 25 wherein said first gas is an inert gas.
27. (Original) The process of claim 26 wherein said inert gas is nitrogen.
28. (Original) The process of claim 25 wherein said first gas is heated.
29. (Original) The process of claim 25 further comprising re-evacuating said process chamber subsequent to said inputting a first gas into said process chamber.
30. (Original) The process of claim 29 wherein said re-evacuating said process chamber evacuates said process chamber to a second pressure.
31. (Original) The process of claim 30 wherein said second pressure is lower than said first pressure.
32. (Original) The process of claim 20 further comprising:
- supplying a second chemical to a heated vaporization chamber;
 - vaporizing said second chemical; and
 - supplying the vapor of said second chemical to said process chamber.

33. (Original) The process of claim 20 wherein said vaporizing said first chemical occurs in a first vaporization chamber.
34. (Original) The process of claim 33 wherein said vaporizing said first chemical comprises heating said first chemical.
35. (Original) The process of claim 33 wherein said vaporizing said first chemical comprises exposing said first chemical to reduced pressure.
36. (Original) The process of claim 34 wherein said vaporizing said first chemical further comprises exposing said first chemical to reduced pressure.
37. (Original) The process of claim 32 wherein said vaporizing said first chemical occurs in a first vaporization chamber.
38. (Original) The process of claim 37 wherein said vaporizing said second chemical occurs in said first vaporization chamber.
39. (Original) The process of claim 38 wherein said vaporizing said first chemical and said vaporizing said second chemical occur relatively simultaneously.
40. (Amended) A process for the coating of a substrate comprising:
- inserting a substrate into a process chamber;
 - dehydrating said substrate;
 - delivering a first amount of a first chemical to a vaporization chamber;
 - vaporizing said first chemical; and

delivering the vaporized first chemical into said process chamber, thereby coating said substrate with said first chemical.

41. (Original) The process of claim 40, wherein said substrate comprises glass.
42. (Original) The process of claim 40, wherein said first chemical comprises silane.
43. (Original) The process of claim 42 wherein said silane is an amino silane.
44. (Original) The process of claim 42 wherein said silane is an epoxy silane.
45. (Original) The process of claim 42 wherein said silane is a mercapto silane.
46. (Original) The process of claim 40 wherein said delivering a first amount of a first chemical to a vaporization chamber comprises:

 withdrawing a first amount of a first chemical from a first chemical reservoir; and

 delivering said first amount of a first chemical to said vaporization chamber.
47. (Original) The process of claim 46 wherein said chemical reservoir is a chemical source bottle.
48. (Original) The process of claim 46 further comprising replacing the lost volume of chemical in the first chemical reservoir with an inert gas.
49. (Original) The process of claim 48 wherein said inert gas is nitrogen.
50. (Original) The process of claim 46 wherein said withdrawing a first amount of a first chemical comprises withdrawing said first amount using a syringe pump.